DEC 2 3 2002

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

DOCKET NO.:

005643 USA/CPI/L/B/PJS

Disclosure Information Statement

SERIAL NO.: APPLICANT: 09/880,465 Seutter, et al.

FILING DATE:

June 12, 2001

GROUP:

U.S. PATENT DOCUMENTS								
Examiner	Document	Date	Name			Class	Subclass	Filing Date
Initial	Number <b>6218301</b>	04/17/01	Yoon	et	al.	438	685	07/31/00
111		PATENT OR PUR	TTSHED	FOR	REIO	N PATE	NT APPLICAT	ION
1420	FOREIGN 1	ALENI OR TO						
Publication: European Patent Application Translation: English Document Number: 0 514 032 A1 Date: November 19, 1992 Country: European countries Class Or Subclass: B32B 15/04 Yes No X								
Patent: Yes NO X  Title: Chemical Vapor Deposition of Diamond Coatings on Hard Substrates								
OTHER DOCUMENTS (Including Author, Title, Date, Place of Publication)  Mark.K. Lai and H.H. Lamb. Tungsten Chemical Vapor Deposition Using Tungsten Hexacarbonyl: Microstructure of As-Deposited and Annealed Films. Thin Solid Films, Vol. 370, No. 1-2, pgs. 114-121 (2000).								
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